The Number Pite Search Text 1	L Number	1 11 L	Coonsh Mout	l pp	l m:
### ### ### ### ### ### ### ### ### ##		4			
2	*		mryakawa.in. and prasma	1	2004/03/20 12:34
5	2	42	miyakawa.in. and plasma	t .	2004/09/28 12:40
With pressure with cluster)					
7 63 (atmospher\$3 with pressure with plasma) and (((1187)) or (1567345.31) or	6	5		USPAT;	2004/09/28 12:44
and ((((118/719) or (156/345.31) or (156/345					
(156/345.32) or (141/939)).CCLS.) O ((118/719) or (156/345.31) or (156/345.31) or (156/345.31) or (156/345.32) or (141/939)).CCLS.) O ((118/719) or (156/345.31) or (156/345.32) or (141/939)).CCLS. O (118/719) or (156/345.31) or (156/345.32) or (141/939)).CCLS. O (118/719) or (156/345.31) or (156/345.32) or	/	63			2004/09/28 12:45
0				US-PGPUB	
(156/345.32) or (414/9391).CCLS.) and ((anneal\$3 hats\$s) with sitylation with curs³1) - 0 ((1618/719) or (156/345.31) or (156/345.32) or (156/345.32) or (141/9391).CCLS.) - 109/502,126 - 3534 atmospher\$3 with pressure with plasma - 109/502,126 - 3504 (1187/19) or (156/345.31) or (156/345.32) or (144/9391).CCLS 0 (414/9391).CCLS 0 (414/9391).CCLS.) - 0 (414/9391).CCLS.) - 0 (1187/19) or (156/345.31) or (156/345.32) or (156/345.32) or (156/345.32) or (156/345.31) or (156/345.32) or (156/345.31) or (156/345.31) or (156/345.32) or (156/345.31)	_	0		USPAT:	2003/05/13 11:25
Cut 33 0 ((136/345.31) or (156/345.31) or (156/345.32) or (141/9391).CCLS.) and (cur 33) cut 33				1	
0					
1.156/345.32 or (414/939)).CCLS.) and (anneal33 heat\$s) same silylation same cur\$3)			1 ' '	TIG DAM	0002/05/12 11 20
CannealS3 heat\$s) same silylation same cur\$3 09/502,126 USPAT; US-PGFUB USPAT;	_	0			2003/05/13 11:32
1 09/502,126 USPAT; US-PGPUB USPAT; US-P				OB IGIOD	
1709 ((118/719) or (156/345.31) or (156/345.32) (156/345.32) or (414/339). CCLS.					
3534 atmospher\$3 with pressure with plasma USPAT; 2003/05/13 11:26 1709 ((118/719) or (156/345.31) or (156/345.32) 0	-	1	09/502,126		2003/05/13 11:23
1709		2524		1	0000 (05 (10 11 11
1709	-	3534	atmospher\$3 with pressure with plasma	1 '	2003/05/13 11:26
Or (144/939)).CCLS.	_	1709	((118/719) or (156/345.31) or (156/345.32)		2003/05/13 12.34
Sol	,				2000/00/13 12.34
(156/345.32) or (414/939).CCLS.) USPAT 2003/05/13 11:30 11:30	– .	50		USPAT;	2004/09/28 12:44
- 6 5578130.URPN. USPAT (156/345.32) or (1414/939).CCLS.) and (156/345.32) or (414/939).CCLS.) and (156/345.32) or (414/939).CCLS.) and (156/345.32) or (414/939).CCLS.) and (156/345.32) or (414/939).CCLS.) and (156/345.32) or (156/3				US-PGPUB	
3	_	_		HCDAM	2002/05/12 11 22
(156/345.32) or (414/939)).CCLS.) and ((anneal\$3 heat\$s) same silicon same cur\$3) 49 (cur\$3.with chamber) and (anneal\$3 with chamber) and ((silicon silylation) with uspequence chamber) and ((silicon silylation) with uspequence chamber) 8 ("4944895" "5047369" "5858457" UspAT 2003/05/13 12:17 UspAT "5958577" "6048804" "615351" "6218302" "6224862").PN. 1 1 "high pressure deposition module" UspAT; 2003/05/13 12:33 UspAT; 2003/05/13 12:33 UspAT; 2003/05/13 12:33 UspAT; 2003/05/13 12:34 UspAT; 2003/05/13 12:44 UspAT; 2003/05/13 12:45 UspAT; 2003/05/13 13:05 UspAT; 2003/05/13 15:34 UspAT; 2003/05/13 15:35 UspAT; 2003/05/13 15:35 UspAT; 2003/05/13 15:35 UspAT; 2003/05/13 15:36 UspAT; 2003/05/13 15:40 UspAT;	_			1	
((anneal\$3 heat\$s) same silicon same cur\$3) (cur\$3.with chamber) and (anneal\$3 with chamber) and (silicon silylation) with chamber) 8 ("4944895" "5047369" "5858457" US-PGPUB "5958577" "6048804" "6153511" USPAT; US-PGPUB 1374 "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (1414/939)).CCLS.) 17 "APCVD" with plasma uspar; US-PGPUB 18 ("APCVD" with plasma uspar; US-PGPUB 19 "silylation chamber" uspar; US-PGPUB 464 "APCVD" with plasma uspar; US-PGPUB 10 ("APCVD" with plasma) and (((118/719) or (156/345.32) or (156/345.32) or (156/345.32) or (156/345.32) or (156/345.32) or (156/345.32) or (156/345.33) or (156/345.32) or (156/345.33) or (156/345.32) or (156/345.33) or (156/345.32) or (156/345.33) or				· ·	2003/03/13 11.34
49 (cur\$3 with chamber) and (anneal\$3 with chamber) and ((silicon silylation) with chamber) (silicon silylation) with uspat; (silydation) with chamber (silicon silylation) with uspat; (silydation) with (silicon) (silydation) with (silicon) (silylation) with (silicon) (silylation)			((anneal\$3 heat\$s) same silicon same		
Chamber and ((silicon silylation) with chamber					
Chamber "5047369" "5858457" USPAT 2003/05/13 11:57 "5958577" "6048804" "6153511" "6218302" "6284682") PN. USPAT USPAT 2003/05/13 12:33 USPAT USP	-	49	(and (and a decire of)	1	2003/05/13 12:17
8		-		US-PGPUB	
"5958577" "6048804" "615351" "6218302" "62284682").PN. "high pressure deposition module" "APCVD" "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) "APCVD" with plasma "APCVD" with plasma) and (((118/719) or (156/345.31) or (156/345.32) or (156/34	_	8	·	 USPAT	2003/05/13 11:57
"6218302" "6284682") PN. "high pressure deposition module" "APCVD" "APCVD" "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) "APCVD" with plasma "APCVD" with plasma "APCVD" with plasma) and (((118/719) or (156/345.32) or (164/939).CCLS.) "The proposition module" "APCVD" with plasma and ((118/719) or (156/345.31) or (156/345.32) or (156/345.32	ļ		"5958577" "6048804" "6153511"		2003/03/13 11.3/
1374			"6218302" "6284682").PN.		,
1374	_	1	"high pressure deposition module"		2003/05/13 12:33
Tabel Tabe	_	1374	"א פרזים"	1	2002/05/12 10:20
17	1	13/4	111 0 4 17	· ·	2003/05/13 12:39
1	-	17	"APCVD" and (((118/719) or (156/345.31) or		2003/05/13 12:34
1 ("APCVD" with plasma) and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 9 "silylation chamber"			(156/345.32) or (414/939)).CCLS.)	US-PGPUB	
1 ("APCVD" with plasma) and (((118/719) or (156/345.31) or (156/345.32) or (141/939)).CCLS.)	-	464	"APCVD" with plasma		2003/05/13 12:42
(156/345.31) or (156/345.32) or (414/939)).CCLS.) 9 "silylation chamber" USPAT; US-PGPUB USP	_	1	("APCVD" with places) and (//110/710)	Į.	2002/05/12 12 22
(414/939)).CCLS.) "silylation chamber" USPAT; US-PGPUB U	 			· ·	2003/05/13 12:39
9 "silylation chamber" 44 silylation with chamber 35 (silylation with chamber) not "silylation chamber" ("6451118").PN. 1667 spin with coating with uniform\$3 (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 35 (spin with coating with uniform\$3 with atmoshperic with deposit\$3 35 (spin with coating with uniform\$3 with uniform\$3 with uniform\$3 with uniform\$3 us-pgpub ((118/\$\frac{1}{2}\$) or (414/939)).CCLS.) 35 (spin with coating with uniform\$3 and (118/\$\frac{1}{2}\$) ccls.) 36 (spin with coating with uniform\$3 with uniform\$3 with uniform\$3 with uniform\$3 with uniform\$3 same (18/\$\frac{1}{2}\$) cspin with coating with uniform\$3 and (118/\$\frac{1}{2}\$) cspin with coating with uniform\$3 with uniform\$3 same (18/\$\frac{1}{2}\$) cspin with coating with uniform\$3 with uniform				OD EGEOD,	
- 44 silylation with chamber 35 (silylation with chamber) not "silylation chamber" 1 ("6451118").PN. 1667 spin with coating with uniform\$3 ((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 35 spin with coating with uniform\$3 with atmoshperic with deposit\$3 0 spin with coating with uniform\$3 same (atmoshperic with deposit\$3) 162 (spin with coating with uniform\$3) and (118/\$.ccls.) 163		9		USPAT;	2003/05/13 12:44
35			-	•	
35	_	44	silylation with chamber	i .	2003/05/13 12:44
Chamber"	_	35	(silulation with chamber) not "cilulation	1	2003/05/13 13:05
1					2003/03/13 13:05
Spin with coating with uniform\$3	-	1			2003/05/13 13:05
5 (spin with coating with uniform\$3) and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 0 spin with coating with uniform\$3 with atmoshperic with deposit\$3 US-PGPUB 162 (spin with coating with uniform\$3 same (atmoshperic with deposit\$3) US-PGPUB 162 (spin with coating with uniform\$3) and (118/\$.ccls.) 4 (spin with coating with uniform\$3 with uniform\$3 with uniform\$3 with uniform\$3 and USPAT; (118/\$.ccls.) 2003/05/13 15:35 US-PGPUB					
5 (spin with coating with uniform\$3) and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 0 spin with coating with uniform\$3 with USPAT; 2003/05/13 15:35 atmoshperic with deposit\$3 0 spin with coating with uniform\$3 same (USPAT; 2003/05/13 15:35 us-PGPUB 2003/05/13 15:36 us-PGPUB 2003/05/13 15:36 us-PGPUB 2003/05/13 15:36 us-PGPUB 2003/05/13 15:40 us-PGPUB 2003/	-	1667	spin with coating with uniform\$3	!	2003/05/13 15:34
(((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) spin with coating with uniform\$3 with uspAT; atmoshperic with deposit\$3 spin with coating with uniform\$3 same (UspAT; atmoshperic with deposit\$3) (spin with coating with uniform\$3 and (118/\$.ccls.) (spin with coating with uniform\$3 with uspAT; (118/\$.ccls.) (spin with coating with uniform\$3 with uspAT; (118/\$.ccls.) (spin with coating with uniform\$3 with uspAT; (118/\$.ccls.) atmospheric) and (118/\$.ccls.) ys-PGPUB US-PGPUB US-P	_	_	(anin with goating with unif-		2002/05/12 15 25
156/345.32) or (414/939)).CCLS.) spin with coating with uniform\$3 with atmoshperic with deposit\$3 spin with coating with uniform\$3 same (atmoshperic with deposit\$3) 162 (spin with coating with uniform\$3) and (118/\$.ccls.) (spin with coating with uniform\$3 with (118/\$.ccls.) (spin with coating with uniform\$3 with atmospheric) and (118/\$.ccls.) 3584 plasma with (atmospheric high) with USPAT; US-PGPUB U		ا			2003/05/13 15:37
0 spin with coating with uniform\$3 with USPAT; atmoshperic with deposit\$3 0 spin with coating with uniform\$3 same (USPAT; atmoshperic with deposit\$3) 162 (spin with coating with uniform\$3) and (Spin with coating with uniform\$3) and (Spin with coating with uniform\$3) and (Spin with coating with uniform\$3 with USPAT; (Spin with uniform\$3 with uniform\$3 with USPAT; (Spin with uniform\$3 with uniform\$3 with USPAT; (Spin with uniform\$3 with uniform				OD LGFOD	
atmoshperic with deposit\$3 ous-pgpub spin with coating with uniform\$3 same (] -	0		USPAT;	2003/05/13 15:35
atmoshperic with deposit\$3) (spin with coating with uniform\$3) and USPAT; 2003/05/13 15:40 USPAT; US-PGPUB (118/\$.ccls.) (spin with coating with uniform\$3 with USPAT; 2003/05/13 15:40 USPAT; atmospheric) and (118/\$.ccls.) The stress of t			atmoshperic with deposit\$3	US-PGPUB	
- 162 (spin with coating with uniform\$3) and USPAT; 2003/05/13 15:40 US-PGPUB USPAT; 2003/05/13 15:40 USPAT; 2003/05/13 USPAT; 2003/	-	0		· ·	2003/05/13 15:36
(118/\$.ccls.) (spin with coating with uniform\$3 with USPAT; 2003/05/13 15:40 atmospheric) and (118/\$.ccls.) JS84 plasma with (atmospheric high) with EPO; JPO; 2003/11/18 11:15	<u>_</u>	162			2002/05/12 15 40
4 (spin with coating with uniform\$3 with USPAT; 2003/05/13 15:40 atmospheric) and (118/\$.ccls.) US-PGPUB EPO; JPO; 2003/11/18 11:15		102		· ·	2003/03/13 15:40
atmospheric) and (118/\$.ccls.) JUS-PGPUB plasma with (atmospheric high) with EPO; JPO; 2003/11/18 11:15	-	4			2003/05/13 15:40
,, ,	•		atmospheric) and (118/\$.ccls.)	US-PGPUB	
	-	3584			2003/11/18 11:15
T. F. T.	<u> </u>		pressure	DERWENT	

_		`				
[)	1257	<pre>plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)</pre>	EPO; JPO; DERWENT	2003/11/18 11:29
	-		380	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	EPO; JPO; DERWENT	2003/11/18 11:30
	-		135	film)) and c23c016\$.ipc. (plasma with (atmospheric) with pressure with (coat\$3 deposit\$3 layer film)) and	EPO; JPO; DERWENT	2003/11/18 12:17
	-		30	c23c016\$.ipc.	EPO; JPO; DERWENT	2003/11/18 11:20
	_		3232	(semiconductor dielectric)) and c23c016\$.ipc. plasma with (atmospheric high) with	исрат.	2002/11/10 11 00
				pressure with (coat\$3 deposit\$3 layer film)	USPAT; US-PGPUB	2003/11/18 11:29
	-		20	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 118/\$.ccls.	EPO; JPO; DERWENT	2003/11/18 12:59
	-		330	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 118/\$.ccls.	USPAT; US-PGPUB	2003/11/18 12:59
	-		2	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	USPAT; US-PGPUB	2003/11/18 11:31
	_		135	film)) and 414/\$.ccls. (plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	USPAT; US-PGPUB	2003/11/18 11:31
	-		41	film)) and 156/345.\$.ccls. (plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	USPAT; US-PGPUB	2003/11/18 11:31
	-		1	film)) and 118/719.ccls. ("5319247").PN.	USPAT; US-PGPUB	2003/11/18 11:53
	-		33 1154	5319247.URPN. "atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer)	USPAT USPAT;	2003/11/18 11:45 2003/11/18 11:54
	-		376	"atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer)	US-PGPUB EPO; JPO; DERWENT	2003/11/18 11:54
	_	e	34	("atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer)) same semiconductor	EPO; JPO; DERWENT	2003/11/18 11:54
	-		215	("atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer)) same semiconductor	USPAT; US-PGPUB	2003/11/18 11:59
	-		330	<pre>(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 118/\$.ccls.</pre>	USPAT; US-PGPUB	2003/11/18 12:17
			2	(in\$1line same cluster) and c23c016\$.ipc.	EPO; JPO; DERWENT	2003/11/18 12:18
	_		9 24	(in\$1line same cluster) and 118/719.ccls.	USPAT; US-PGPUB	2003/11/18 12:18
	_		18	(plasma with "atmospheric pressure") and 118/719.ccls. 5651867.URPN.	USPAT; US-PGPUB	2003/11/18 13:53
	-		1	("6342275").PN.	USPAT USPAT; US-PGPUB	2003/11/18 13:07 2003/11/18 14:56
	_		. 669	"18249" miyakawa.in.	EPO; JPO; DERWENT	2003/11/18 14:56
	_		10	miyakawa.in. and plasma	EPO; JPO; DERWENT EPO; JPO;	2003/11/18 14:56
	_		26	barnes-michael.in. cox-michael-s\$.in.	DERWENT EPO; JPO;	2003/11/18 15:02
			58	<pre>lai-canfeng.in. parks-joun.in. barnes-michael.in. cox-michael-s\$.in. lai-canfeng.in. parks-joun.in.</pre>	DERWENT USPAT; US-PGPUB	2003/11/18 15:02
	-		10	"electromagnetic wave marker"	EPO; JPO; DERWENT	2003/11/18 16:48
	_		1 0	"electromagnetic wave marker"	USPAT; US-PGPUB	2003/11/18 16:49
L			. U	"electromagnetic wave" with lane\$1marker	USPAT; US-PGPUB	2003/11/18 16:49

4.	_	27	"electromagnetic wave" with lane	USPAT; US-PGPUB	2003/11/18 16:50
	-	9	plasma and ((atmospheric ambient high) with pressure with cluster)	EPO; JPO; DERWENT	2004/06/08 15:53
	-	22	plasma and ((atmospheric ambient high) with pressure) and cluster	EPO; JPO; DERWENT	2004/06/08 15:53
	-	3747		USPAT; US-PGPUB	2004/06/08 15:53
	- .	847	(plasma same ((atmospheric ambient high) with pressure)) and cluster	USPAT; US-PGPUB	2004/06/08 15:54
	-	36	(plasma same ((atmospheric ambient high) with pressure)) same (cluster with (tool	USPAT; US-PGPUB	2004/06/08 16:23
	-	14	"4523897" "4640667" "4718836" "5009575" "5165864" "5238362"	USPAT	2004/06/08 16:03
Í	_	0	"5672322" "5803713" "5820354" "5871336" "6179573").PN. 6736606.URPN.		
	-	0	"apcvd" same cluster same plasma	USPAT USPAT; US-PGPUB	2004/06/08 16:12 2004/06/08 16:24
	_	0	"apcvd" same cluster same plasma	EPO; JPO; DERWENT	2004/06/08 16:24
	_	14	"apcvd" same plasma	EPO; JPO; DERWENT	2004/06/08 16:25
	_	825	"apcvd" same plasma	USPAT; US-PGPUB	2004/06/08 16:25
	-	7	<pre>"apcvd" same plasma same ((cluster)((multiple plural\$3 several) with (chamber apparatus units)))</pre>	USPAT; US-PGPUB	2004/06/08 16:31
	_	728676	("apcvd" same plasma) and (silicon and valley).as. ((cluster)((multiple plural\$3	USPAT; US-PGPUB	2004/06/08 16:32
	-	7	several) with (chamber apparatus units))) ("apcvd" same plasma) and (silicon and valley).as.	USPAT;	2004/06/08 16:32
	-	7	("apcvd" same plasma) and (valley).as.	US-PGPUB USPAT;	2004/06/08 16:32
	<u>-</u>	. 1	("6143080").PN.	US-PGPUB USPAT;	2004/06/09 13:15
	-	2	(("4834020") or ("5136975")).PN.	US-PGPUB USPAT;	2004/06/09 13:15
	-	10	("4834020" "5136975" "5413671" "5683516" "5776254" "5849088" "5863337" "5888579" "5976258"	US-PGPUB USPAT	2004/06/09 13:17
-	-	. 1	"6022414").PN. ("6451118").PN.	USPAT;	2004/06/09 15:53
-	-	5.	118/718.ccls. and (spin with coat\$3)	US-PGPUB USPAT;	2004/06/09 15:05
-	-	42	(US-5863338-\$ or US-5626677-\$ or US-5587207-\$ or US-5578130-\$ or	US-PGPUB USPAT;	2004/06/09 15:20
			US-6559070-\$ or US-6562128-\$ or US-6338756-\$ or US-6001739-\$ or US-6451118-\$ or US-5743965-\$ or US-5562772-\$ or US-5099782-\$ or	US-PGPUB; EPO; JPO; DERWENT	
			US-4640846-\$ or US-5319247-\$ or US-6342275-\$ or US-6143080-\$ or US-5605867-\$ or US-5484749-\$ or		
			US-5041304-\$ or US-4003770-\$ or US-6207005-\$ or US-6627039-\$ or US-6736606-\$ or US-6026589-\$ or US-5776254-\$).did. or (US-20030039766-\$ or		
	-		US-20020134310-\$ or US-20020197878-\$ or US-20030106791-\$ or US-20030044154-\$).did. or (WO-9518249-\$).did. or (JP-2001168029-\$		
			or JP-2001035835-\$ or JP-08298245-\$ or JP-06330326-\$ or JP-06041755-\$ or JP-01306569-\$ or JP-08203891-\$).did. or (EP-678914-\$ or DE-4135810-\$ or		
L			EP-431951-\$ or US-6342275-\$).did.		į.

- •	0	((US-5863338-\$ or US-5626677-\$ or	USPAT;	2004/06/09 15:20
		US-5587207-\$ or US-5578130-\$ or	US-PGPUB	
		US-6559070-\$ or US-6562128-\$ or		
		US-6338756-\$ or US-6001739-\$ or		
		US-6451118-\$ or US-5743965-\$ or		
		US-5562772-\$ or US-5099782-\$ or		!
		US-4640846-\$ or US-5319247-\$ or		
		US-6342275-\$ or US-6143080-\$ or		
		US-5605867-\$ or US-5484749-\$ or		
		US-5041304-\$ or US-4003770-\$ or	•	
		US-6207005-\$ or US-6627039-\$ or		
		US-6736606-\$ or US-6026589-\$ or		
		US-5776254-\$).did. or (US-20030039766-\$ or		
		US-20020134310-\$ or US-20020197878-\$ or		
		US-20030106791-\$ or US-20030044154-\$).did.		
		or (WO-9518249-\$).did. or (JP-2001168029-\$		
		or JP-2001035835-\$ or JP-08298245-\$ or		
		JP-06330326-\$ or JP-06041755-\$ or		
		JP-01306569-\$ or JP-08203891-\$).did. or		ŀ
		(EP-678914-\$ or DE-4135810-\$ or		1
		EP-431951-\$ or US-6342275-\$).did.) and		
		imahashi.in.		
_	2	118/719.ccls. and imahashi.in.	USPAT;	2004/06/09 15:24
			US-PGPUB	
-	10	118/719.ccls. and ((atmospheric high) with	USPAT:	2004/06/09 15:25
		pressure with cluster)	US-PGPUB	= = = = = = = = = = = = = = = = = = =
_	5	(204/298.25.ccls.) and ((atmospheric high)	USPAT;	2004/09/28 12:44
		with pressure with cluster)	US-PGPUB	
_	1	("6143080").PN.	USPAT;	2004/06/09 16:00
		,	US-PGPUB	=====================================
_	2	(("5683516") or ("5849088")).PN.	USPAT;	2004/06/09 16:00
			US-PGPUB	2001/00/05 10:00